

Spin Rinser Dryer SRD-50 / 100 High process quality coupled with high productivity



Wafer Clean	Photoresist	Mask Alignment	Post Bake	Etch &	Stripping	Clean &
& Primer	& Soft Bake	& Exposure	& Develop	Hard Bake		Inspection
Spin Rinser Drye Hotplates (Dehumidifier)	Spin Modules Spray Coater Hotplates		Hotplates Developer	Developer Developer-Etch Hotplates	Developer-Etch	Spin Rinser Dryer

The SAWATEC spin rinser dryers are equipped with closed stainless steel process chambers. The SRD-series is characterized by its excellent process quality and high productivity.

The **Spin Rinser Dryer SRD-50 and SRD-100** are easy to operate and to handle. With this cooling and drying centrifuge, wafers or substrates can be cleaned following wet-chemical processes and dried efficiently with the aid of centrifugal force and heated nitrogen.

The process chamber respectively the cassette rotor is designed for a substrate diameter of 40mm, with a maximum load capacity of 6 wafer cassettes, each containing up to 36 wafers (SRD-50) or for substrate sizes from 4", 6" to 8" in one carrier holding up to 25 wafers (SRD-100).

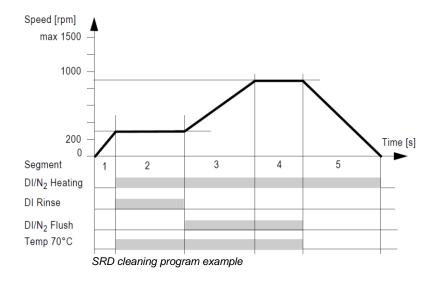
The instrument is available as a bench mounted version.

FEATURES (BASIC CONFIGURATION)

- Up to 20 programmes with 24 segments each can be programmed
- Quick start function for repeat processes
- User-friendly process configuration with touch screen panel
- Process parameters: speed, rins and dry time, rins and dry temperature, process chamber temperature
- Cassettes fixation mechanically
- Pneumatic driven cover with two hand operation
- Manual loading and unloading of the cassettes
- Acoustic signal when process has finished



Touch Screen and quick start button





Spray nozzle

PERFORMANCE DATA

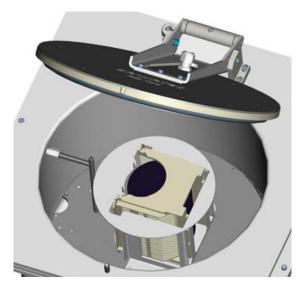
- Loading capacity: Max. 36 wafers per cassette, totally 6 cassettes (SRD-50)
- Loading capacity: Max. 25 wafers per cassette (4-8"), one central carrier (SRD-100)
- Speed range: 0 to 1'500rpm +/-1rpm
- Rins time: 99 seconds/segments
- N2 dry time: 99 seconds/segments
- Rins and dry temperature: up to 80°C
- Process chamber temperature: up to 70°C

ADDITIONAL FUNCTIONS (OPTIONS)

- DI water conductance measurement allows rinsing up to a certain resistance
- Antistatic device



The SRD-50 cassette rotor can be used with 6, 4, 3 or 2 cassettes (each cassette needs same filling)

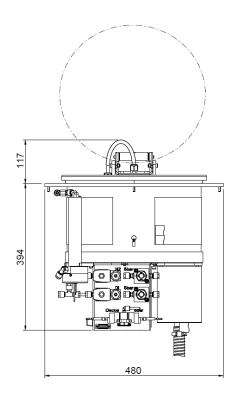


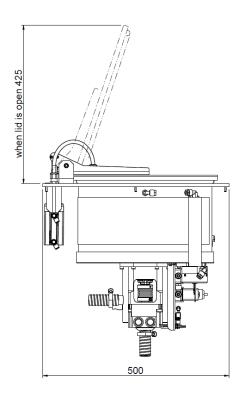
Customized cassette carrier (SRD-100) for wafers up to 8"

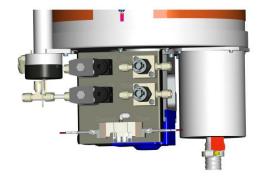
DESIGN AND DIMENSIONS

- Compact, space-saving design
- Closed process chamber made of electro-polished stainless steel
- Electro-polished stainless steel rotor 3.5" colour display touch screen panel
- Dimensions: 480 x 500 x 511mm (L x B x H)
- Weight: approx. 65kg

front view



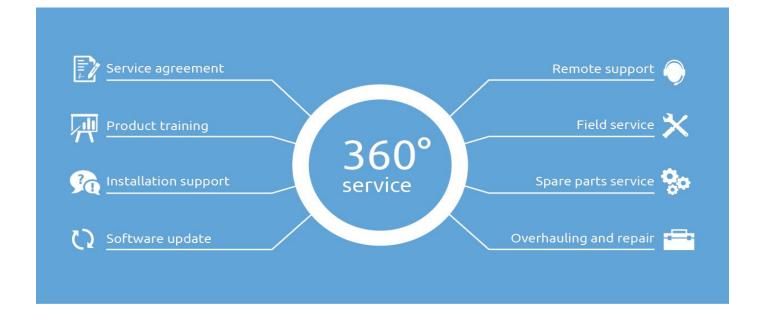




REQUIRED MEDIA

- 3x 400 VAC 50/60Hz 16A
- Compressed dry air tube Ø10/8mm (5 bar)
- N2 tube Ø10/8mm (5 bar)
- DI water tube Ø8/6mm (5 bar)
- Exhaust connector Ø25mm
- Sewage connector Ø25mm





If you would like a personal consultation or have a specific request, please do not hesitate to call us. Our technical experts will be pleased to help you.

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